

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-10693 US		Unknown	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicants: Steve Biellak, et al.			
(Use several sheets if necessary)					Filing Date: June 26, 2001			
					Group: Unknown 2877			
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
HP	AA	4,449,818	5/1984	Yamaguchi				
HP	AB	4,794,265	12/1988	Quackenbos et al.				
HP	AC	4,893,932	1/1990	Knollenberg				
HP	AD	4,898,471	2/1990	Stonestrom et al.				
HP	AE	4,929,845	5/1990	Amir et al.				
HP	AF	5,058,982	10/1991	Katzir				
HP	AG	5,389,794	2/1995	Allen et al.				
HP	AH	5,424,838	6/1995	Siu				
HP	AI	5,530,550	6/1996	Nikoonahad et al.				
HP	AJ	5,650,614	7/1997	Yasutake et al.				
HP	AK	5,798,829	8/1998	Vaez-Iravanj				
HP	AL	5,416,594	5/1995	Gross et al.				
HP	AM	6,201,601 B1	3/2001	Vaez-Iravani et al.				
HP	AN	09/746,141	12/21/00					
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
HP	AO	WO97/33158	9/1997	International			X	
HP	AP	EP0624787	11/1994	Europe			X	
HP	AQ	DE4123916	1/1992	German				X
HP	AR	WO97/12226	4/1997	International			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
HP	AS	"Surface Inspection System for Estimation of Wafer," Y. Yatsugake et al., <i>Hitachi Electronics Engineering Technical Report</i> , Vol. 11, January 1996, pp. 21-26						
HP	AT	Figure, Hitachi Electronics Engineering Co., Ltd., presented by Etsuro Morita of Mitsubishi Materials Silicon Corp. in a presentation entitled "Exploration of COP and COP Defect Crystal Originated 'Particles,'" at the 6 th International Workshop on 300 Millimeter Wafers on 12/5/1996 in Makuhari, Japan						
HP	AU	Partial European Search Report dated October 18, 2000						
Examiner <i>HP</i>			Date Considered <i>1/22/02</i>					
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								

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